

FIG. 1
PRIOR ART

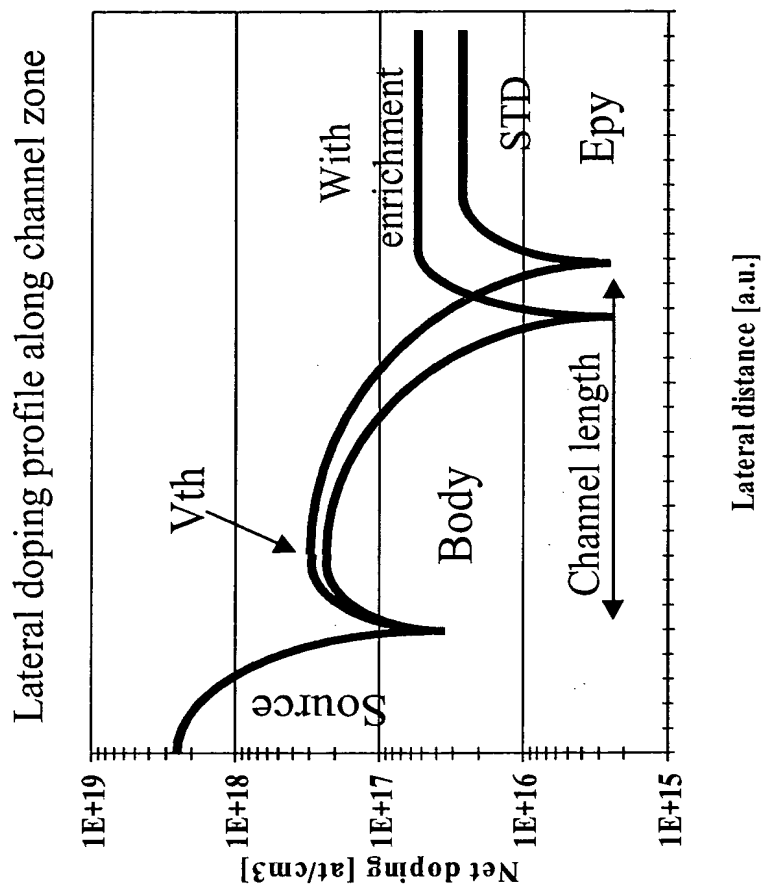
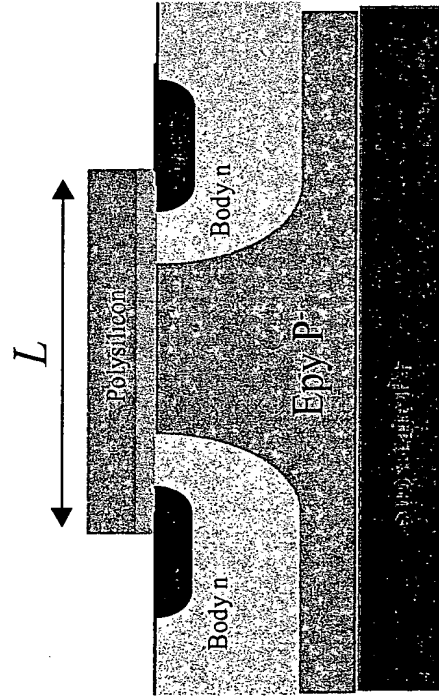
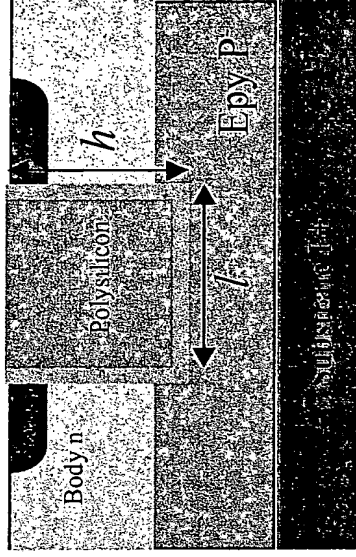


FIG. 3

STD




Trench



Gate area $\propto L$

Gate area $\propto (l + 2h)$

FIG. 4

1 

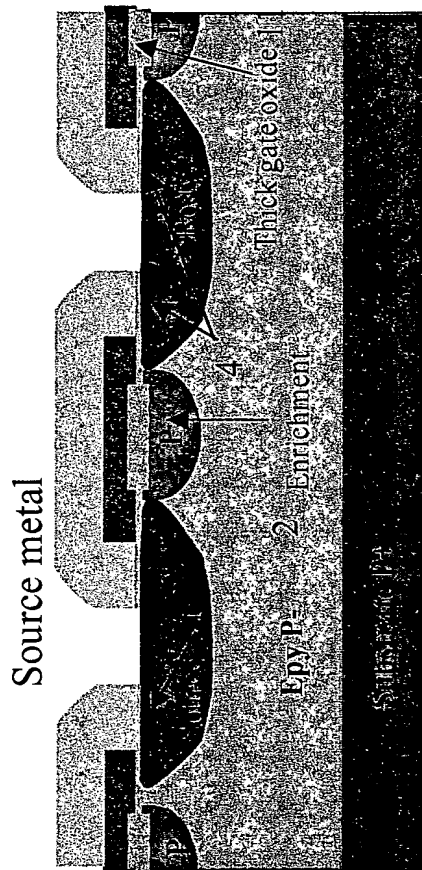


FIG. 5

Enrichment implant

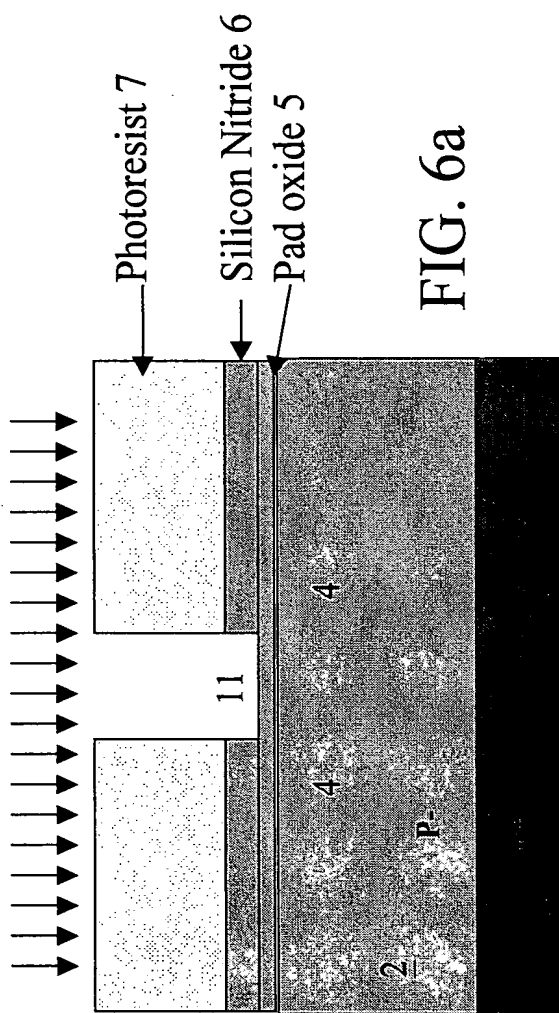


FIG. 6a

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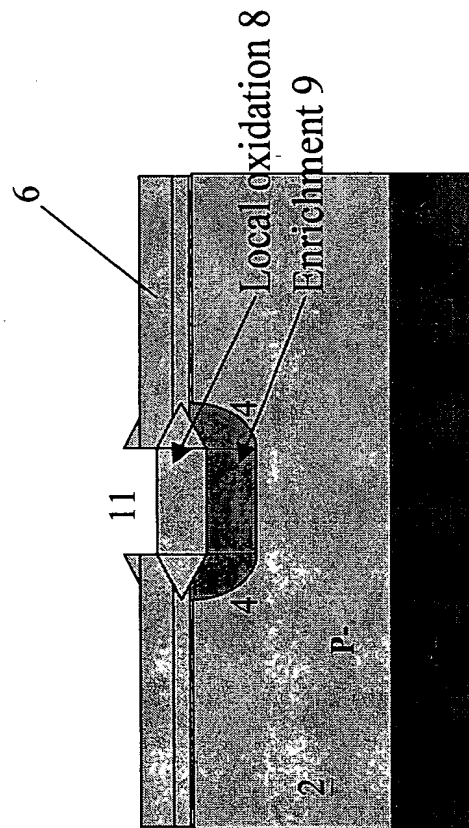


FIG. 6b

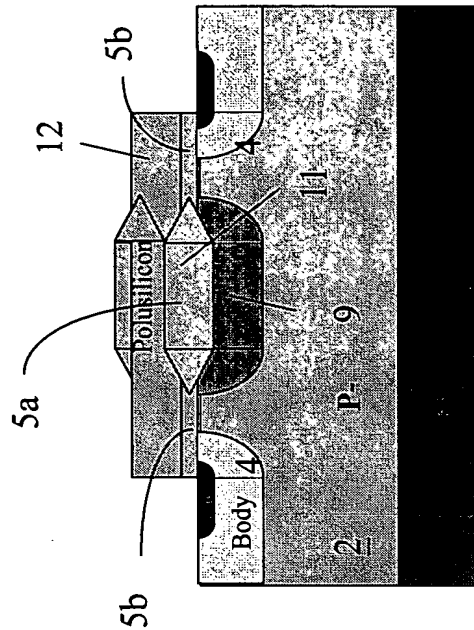


FIG. 6c

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Enrichment implant

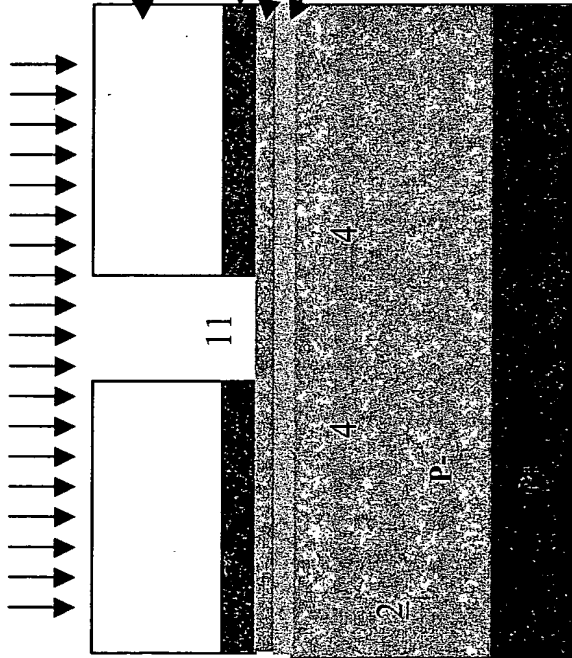


FIG. 7a

Photoresist 7
Silicon Nitride 6
Polysilicon 13
Gate oxide 5

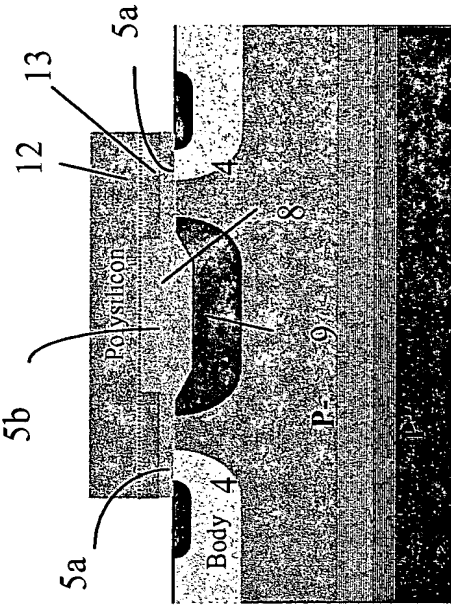


FIG. 7c

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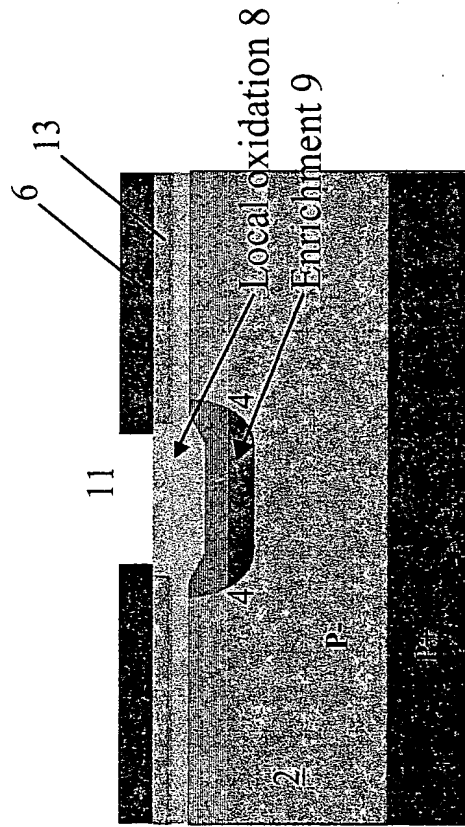


FIG. 7b

Local oxidation 8
Enrichment 9

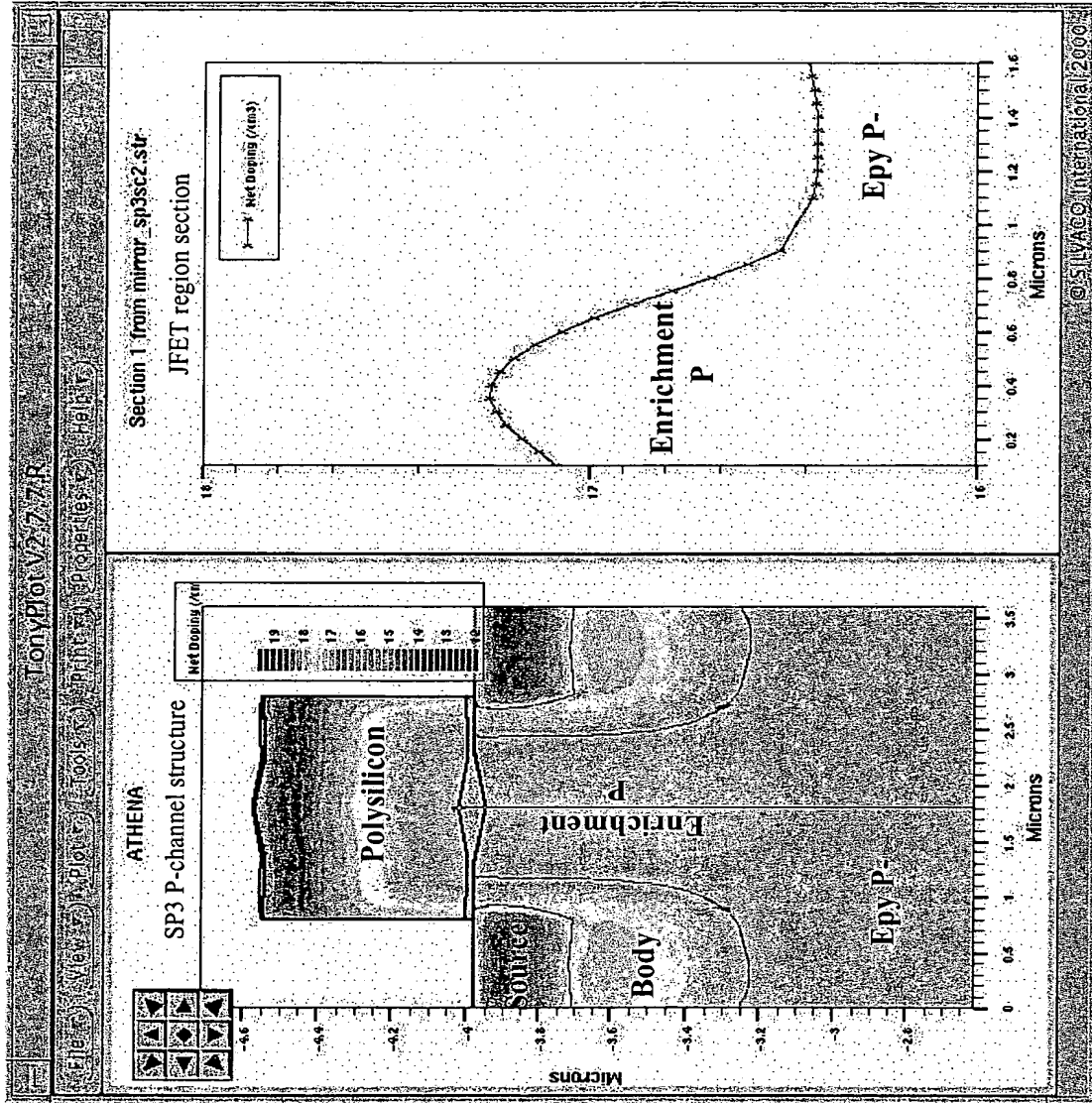


FIG. 8